>>>> 会议日程 CONFERENCE AGENDA <<< August 3-4, 2025, Banyan Tree Tianjin Riverside, Tianjin, China

(August 2 is for registration)

r rogram Ch	airs: Xinyu Liu, Tadatomo Suga, Xiaohua Ma August 2, 2025 (Saturday)				
10:30-20:00					
Day1: August 3, 2025 (Sunday) 2F Banyan Ballroom					
08:30-08:45	Opening Remarks Chair: Xinyu Liu				
08:45-09:00	Conference Overview Chairs: Tadatomo Suga, Xiaohua Ma				
09:00-09:30	(Keynote) Surface Activated Bonding - History, Current Status, and Future outlook				
09:30-10:00	Tadatomo Suga, The University of Tokyo/Meisei University/IMSI, Japan (Keynote) New Progress in Wide-Bandgap Semiconductor Devices and Chips				
10:00-10:30	Yue Hao(郝 跃), Xidian University (Keynote) Heterogeneous Integration and Packaging Manufacturing of Chips				
10:30-10:50	Sheng Liu(刘 胜), Wuhan University				
Plenary Session I: Surface Activated Bonding and Its Extensions					
Chairs: Tadat	omo Suga, Liangxing Hu (虎良省) (Keynote) Recent Advances in Atomic Diffusion Bonding: Bonding				
10:50-11:20					
11:20-11:40	(Invited) Large Area 5J Solar Cells Based on the Direct Bonded Process He Wang(王 赫), Tianjin Institute of Power Source				
11:40-11:50	Lowering thermal boundary resistance at bonded heterogeneous interfaces by surface-activated bonding Rulei Guo(郭汝磊), The University of Tokyo				
11:50-12:00	N Polar GaN-AlN-Diamond structure fabricated by modified surface active bonding and selective dry Ye Tian(田 野), Institute of Microelectronics of the Chinese Academy of Sciences				
12:00-12:10	High Bonding Strength of GaN and Diamond through Optimization of Bonding Area				
12:10-12:20					
12:20-13:30	Xin Chen(陈鑫), Nanjing Electronic Devices Institute Lunch				
-	ession II: Hybrid Bonding and 3D integration				
Citalis, Wel V	Vang(王 玮), Yunwen Wu(吴蕴雯) (Keynote) Flip 3D (F3D): A Novel 3D Integration Technology Enabled by				
13:30-14:00	the Advanced Bonding Heng Wu(吴恒), Peking University				
14:00-14:30	(Keynote) Enabling Technologies and 3D Integration for Edge AI Microsystems Chengkuo Lee(李正国), National University of Singapore				
14:30-14:50	(Invited) Low-temperature Cu/SiO ₂ and Co/SiO ₂ hybrid bonding for high-density interconnection				
14:50-15:10	Chenxi Wang(王晨曦), Harbin Institute of Technology (Invited) Interface Investigation for Hybrid Bonding Interconnects Qidong Wang/Renxi Jin(王启东/金仁喜), Institute of Microelectronics of the Chinese				
15:10-15:25	Academy of Sciences 3D heterogeneous integration for GaN HEMT and CNTFET Bowen Zhang(张博文),Xidian University				
15:25-15:40	Coffee Break				
Plenary Se Materials	ession III: Novel Low Temperature Bonding Processes and				
	eng Zou(邹贵生), Ryo Takigawa				
15:40-16:00	(Invited) Spontaneous Formation of SiO₂ Bonding Interface via Polysilazane Conversion Kai Takeuchi, Tohoku University, Japan				
16:00-16:20	(Invited) Low Temperature Bonding Based on Electrodeposited Perpendicularly Nanotwinned Cu Yunwen Wu(吴蕴雯), Shanghai Jiao Tong University				
16:20-16:40	(Invited) Low Temperature Nanojoining for Device Integration Lei Liu(刘 磊), Tsinghua University				
16:40-17:00	(Invited) Recent Progress in Ag-In Transient Liquid Phase Bonding Technologies for Next-Generation Optoelectronic Systems				
17:00-18:00	Yongjuan Huo(霍永隽), Beijing Institute of Technology Poster session				
18:00-20:00	Banquet				
	Day2: August 4, 2025 (Monday)				
	2F Banyan Ballroom				
Application	ession IV: Power, RF, Photonics, MEMS and Displays devices ons (1) gurashi, Qian Wang(王 谦)				
08:30-09:00	(Keynote) Fusion of GaN and SiC for High-Performance Power Devices Kevin Jing Chen(陈 敬), The Hong Kong University of Science and Technology				
09:00-09:20	(Invited) Room-Temperature Bonding of Polycrystalline Diamond and				
09:20-09:40					
09:40-09:55	Ailun Yi(伊艾伦), Shanghai Institute of Microsystem and Information Technology, Chinese Academy of Sciences				
09:55-10:10	Xingye Zhou(周幸叶), Hebei Semiconductor Research Institute				
10:10-10:25	High-Performance CMOS-compatible RF GaN-based HEMT technology using Gold-free Technology Hao Lu(芦 浩), Xidian University				
10:25-10:40	Coffee Break				
Plenary Session V: Fundamental Principles and Characterization Chairs: Jiandong Vo. (吐建车) Fujun Vu. (许福军)					

Plenary Session	V: Fundar	mental	Principles	and	Characteriza	ation
Chairs: Jiandong Ye	(叶建东),	Fujun Xu	(许福军)			

Zhe Cheng (程 哲), Peking University

and temperature characterization

Chao Yuan (袁 超), Wuhan University

(Keynote) 3DIC Multi wafer hybrid bonding process technology challenge

Sheng Hu(胡 胜), Wuhan Xinxin Semiconductor Manufacturing Co., Ltd. (XMC)

(Invited) Heterogeneous integration of high-thermal-conductivity silicon

(Invited) Non-invasive transient thermoreflectance for thermal properties

The Application of Morphological Measurement Technology in LTB-3D

Application of Ultrasonic Scanning Technology in Wafer Level Bonding

Lunch

(Keynote) Wide and Ultrawide Bandgap Semiconductor Electronics: The

Guoyou Liu(刘国友), Southwest Jiaotong University/Zhuzhou CRRC Times Electric

(Invited) Research progress on high-performance millimeter wave GaN RF

(Keynote) Surface Activated Room Temperature Bonding for

(Invited) Power semiconductor and integration technology

Plenary Session VI:	Power, RF, Photonics, MEMS and Displays devices
Applications (2)	

Frank Duan (段忠福), SBT Ultrasonic Technology Co.,Ltd.

Co., Ltd (Invited) Heterointegrated Ga₂O₃-on-SiC RF MOSFETs 14:50-15:10

devices

10:40-11:10

11:10-11:30

11:30-11:50

11:50-12:05

12:05-12:20

12:20-13:30

13:30-14:00

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15:45-16:15

17:40-17:55

carbide

Aris Ma, AK Optics

Chairs: Kevin Jing Chen(陈 敬), Qian Sun(孙 钱)

Importance of Interfaces

Martin Kuball, University of Bristol (UK)

Ryo Takigawa, Kyushu University, Japan

14:00-14:30 Heterogeneous Photonics Integration and Packaging

Jiandong Ye (叶建东), Nanjing University

Ling Yang(杨 凌), Xidian University

Process

15:30-15:45 Coffee Break Plenary Session VII: Heterogeneous Integration and Related Materials

Integration and Advances in Sensors and Electronic Devices

(Keynote) Low-Temperature Bonding Technology for Heterogeneous

Ultrafast planarization of large-scale polycrystalline diamond used for

Xin Ou / Tiangui You(欧 欣/游天桂), Shanghai Institute of Microsystem and Information Technology, Chinese Academy of Sciences

Eiji Higurashi, Tohoku University, Japan (Invited) Heterogeneous integrated materials and devices based on bonding technology 16:15-16:35 (Invited) Investigation of the interfacial bonding strength in heterogeneously integrated materials 16:35-16:55

Dong Liu, University of Oxford (UK)

Chairs: Takehito Shimatsu, Chenxi Wang (王晨曦)

(Invited) The Enabling Role of Publicly Accessible R&D Platforms in 16:55-17:15 Heterogeneous Integration Fei Zhong(钟 飞), Yongjiang Laboratory N-polar GaN/AlGaN Heterostructures Fabricated by Direct Wafer Bonding with Polycrystalline Diamond 17:10-17:25

Qian Li(李倩), Suzhou institute of Nano-Tech and Nano-Bionics, Chinese Academy of Sciences Low-Temperature Integration of InP Heterostructure on Silicon via Surface-Activated Bonding and Selective Wet Etching 17:25-17:40 Xuezheng Gang(刚学正), Institute of Microelectronics of the Chinese Academy of Sciences

Jinxin Zou(邹金鑫), University of Science and Technology Beijing 18:00-19:00 Reception

bonding by microsecond laser